
FOUNDATIONS OF VACUUM SCIENCE AND TECHNOLOGY

EDITED BY

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CONTENTS

Preface	v
Contributors	ix
Acronyms	xxiii
1. Kinetic Theory of Gases <i>Benjamin B. Dayton</i>	1
1.1. Ideal Gas Law / 2	
1.2. Avogadro's Number / 6	
1.3. Molecular Collisions; Mean Free Path; Maxwell-Boltzmann Distribution Laws / 8	
1.3.1. Relation Between Molecular Velocities and Velocity of Sound / 16	
1.3.2. Determination of Avogadro's Constant from Distribution of Particles in Brownian Motion / 17	
1.4. Gas Pressure and Rate at Which Molecules Strike a Surface / 18	
1.5. Rate of Evaporation and Vapor Pressure / 22	
1.6. Free Paths of Molecules / 26	
1.7. Relation Between Coefficient of Viscosity, Mean Free Path, and Molecular Diameter / 29	
1.7.1. Viscosity at Low Pressures / 37	
1.7.2. Molecular Diameters / 39	
1.7.3. Application of the van der Waals Equation / 39	
1.7.4. From the Density of the Solid or Liquid / 40	
1.7.5. Cross Section for Collision with Electrons / 41	
1.8. Heat Conductivity of Gases / 41	
1.9. Thermal Conductivity at Low Pressures / 44	
1.9.1. Free-Molecule Conductivity (Knudsen) / 46	
1.9.2. Temperature Discontinuity (Smoluchowski) / 50	

- 1.10. Thermal Transpiration (Thermomolecular Flow) / 53
 - 1.11. Thermal Diffusion / 57
 - 1.12. Theory of Diffusion of Gases / 62
 - 1.12.1. Maxwell-Loschmidt Method for Determination of Diffusion Coefficients / 65
 - 1.12.2. Effect of Pressure of Gas on Rates of Evaporation of Metals / 67
 - 1.13. Random Motions and Fluctuations / 69
 - 1.14. Scattering of Particle Beams at Low Gas Pressures / 71
- References and Notes / 73

2. Flow of Gases Through Tubes and Orifices

81

R. Gordon Livesey

- 2.1. Flow Conductance, Impedance, and Gas Throughput / 83
- 2.2. Molecular Flow / 85
 - 2.2.1. Conductance of an Aperture / 86
 - 2.2.2. General Considerations for Long Ducts / 87
 - 2.2.3. General Considerations for Short Ducts / 87
 - 2.2.4. Uniform Circular Cross Section / 88
 - 2.2.5. Duct of Uniform Rectangular Cross Section / 90
 - 2.2.6. Tube of Uniform Elliptical Cross Section / 92
 - 2.2.7. Cylindrical Annulus (Flow Between Concentric Cylinders) / 93
 - 2.2.8. Uniform Triangular Section (Equilateral) / 94
 - 2.2.9. Other Shapes / 94
 - 2.2.10. Combinations of Components / 96
 - 2.2.11. Cases of Unsteady Flow / 102
- 2.3. Continuum Flow / 105
 - 2.3.1. Viscous Laminar Flow / 108
 - 2.3.2. Turbulent Flow / 112
 - 2.3.3. Compressible Flow / 116
 - 2.3.3.1. *Flow Through an Aperture or Short Duct* / 119
 - 2.3.3.2. *Approximation for Flow Through an Aperture* / 121
 - 2.3.4. Corrections for Flow Obstructions / 121
 - 2.3.5. Approximations—Entrance Correction Model / 122
 - 2.3.6. Approximations—Kinetic Energy Model / 124
 - 2.3.7. Long Duct Criteria / 126
- 2.4. Transitional Flow / 128
 - 2.4.1. Transitional Flow in Long Ducts / 129
 - 2.4.2. Long Duct Criterion in Transitional Flow / 134
 - 2.4.3. Transitional Flow Through Apertures and Short Ducts / 135

Symbols / 137

References / 139

3.	Positive Displacement Vacuum Pumps	141
Part I.	Oil-Sealed Vacuum Pumps	143
	<i>Nigel T. M. Dennis</i>	
3.1.	Oil-Sealed Vacuum Pumps / 143	
3.1.1.	Pump Design / 143	
3.1.2.	Gas Ballast / 144	
3.1.3.	Pump Oil / 147	
3.1.4.	Oil Suckback / 148	
3.1.5.	Power Requirements and System Protection / 148	
3.1.6.	Accessories / 149	
Part II.	Liquid Ring Pumps	151
	<i>Helmut Bannwarth</i>	
3.2.	Liquid Ring Pumps / 151	
3.2.1.	Mechanism / 151	
3.2.2.	Single-Stage Liquid Ring Vacuum Pumps / 152	
3.2.3.	Two-Stage Liquid Ring Vacuum Pumps / 153	
3.2.4.	The Operating Liquid / 154	
3.2.5.	Operating Ranges of Liquid Ring Gas Pumps / 154	
3.2.6.	Cavitation and Protection Against Cavitation / 154	
3.2.7.	Types of Operation; Conveyance of Operating Liquid / 156	
3.2.8.	Materials of Construction / 157	
3.2.9.	Sealing / 157	
3.2.10.	Drives / 157	
3.2.11.	Accessories / 158	
Part III.	Dry Vacuum Pumps	159
	<i>Nigel T. M. Dennis</i>	
3.3.	Dry Vacuum Pumps / 159	
3.3.1.	Roots Pump / 159	
3.3.2.	Claw Pump / 162	
3.3.3.	Screw Pump / 164	
3.3.4.	Scroll Pump / 167	
3.3.5.	Piston and Diaphragm Pumps / 169	
	References / 170	
	General References / 171	
4.	Kinetic Vacuum Pumps	173
Part I.	Diffusion and Diffusion-Ejector Pumps	175
	<i>Benjamin B. Dayton</i>	
4.1.	Diffusion Pumps / 176	
4.1.1.	History of Development / 176	
4.1.2.	Diffusion Pump Design / 181	

- 4.2. Diffusion-Ejector Pumps / 183
- 4.3. Performance of Vapor-Jet Pumps / 185
 - 4.3.1. Pumping Speed / 185
 - 4.3.2. Limiting Forepressure for Maximum Speed / 187
 - 4.3.3. Influence of Nozzle and Entrance Chamber Design on Speed / 190
 - 4.3.4. Ultimate Pressure / 192
 - 4.3.5. Backstreaming and Back Migration of Pump Fluid / 194
 - 4.3.6. Throughput / 198
- 4.4. Theory of Pump Performance / 202
 - 4.4.1. Speed / 202
 - 4.4.2. Limiting Forepressure / 204
 - 4.4.3. Vapor-Jet Flow Pattern / 205
 - 4.4.4. Ultimate Pressure / 221

Part II. Molecular Drag and Turbomolecular Pumps

233

Jörgen Henning

- 4.5. Molecular Drag Pumps / 233
 - 4.5.1. Theoretical Considerations and Performance Data / 234
 - 4.5.2. Design Considerations / 237
 - 4.5.3. Typical Performance Data of Commerical Pumps / 237
 - 4.5.3.1. *Compression* / 238
 - 4.5.3.2. *Pumping Speed* / 238
 - 4.5.3.3. *Ultimate Pressure* / 238
- 4.6. Turbomolecular Pumps / 238
 - 4.6.1. Theoretical Considerations and Performance Data / 239
 - 4.6.2. Design Considerations / 241
 - 4.6.2.1. *Rotor and Stator Geometry* / 241
 - 4.6.2.2. *Rotor Suspension* / 242
 - 4.6.2.3. *Lubrication of Mechanical Bearings* / 242
 - 4.6.2.4. *Magnetic Rotor Suspension* / 242
 - 4.6.2.5. *Balancing and Vibration* / 243
 - 4.6.2.6. *Rotor Materials* / 243
 - 4.6.2.7. *Drive Systems* / 243
 - 4.6.3. Applicational Considerations / 243
 - 4.6.3.1. *Venting* / 243
 - 4.6.3.2. *Baking* / 244
 - 4.6.3.3. *Cooling* / 244
 - 4.6.3.4. *Operation in Magnetic Fields* / 244
 - 4.6.3.5. *Pumping Corrosive Gases* / 245
 - 4.6.3.6. *Pumping Toxic or Radioactive Gases* / 245
 - 4.6.3.7. *Turbomolecular Pumps in Combination with Other Pumps* / 245

4.6.4.	Performance Data of Commercial Pumps / 245	
4.6.4.1.	<i>Compression</i> / 246	
4.6.4.2.	<i>Pumping Speed</i> / 246	
4.6.4.3.	<i>Ultimate Pressure</i> / 247	
4.7.	Combined Molecular Drag and Turbomolecular Pumps / 247	
4.7.1.	Design Considerations / 248	
4.7.2.	Typical Performance Data for Commercial Combined Molecular Drag and Turbomolecular Pumps / 248	
4.7.2.1.	<i>Compression</i> / 248	
4.7.2.2.	<i>Pumping Speed</i> / 248	
4.7.2.3.	<i>Ultimate Pressure</i> / 248	
4.8.	Backing Pumps / 248	
Part III.	Regenerative Drag Pumps	251
	<i>Nigel T. M. Dennis</i>	
4.9.	Regenerative Drag Pumps / 251	
4.9.1.	Mechanism / 251	
	References / 254	
5.	Capture Vacuum Pumps	259
Part I.	Getters and Getter Pumps	261
	<i>Bruno Ferrario</i>	
5.1.	Types of Gas Surface Interactions / 261	
5.2.	Basic Concepts of Getter Materials / 262	
5.3.	Adsorption and Desorption / 263	
5.4.	Bulk Phenomena / 265	
5.4.1.	Diffusion / 265	
5.4.2.	Solubility / 267	
5.5.	Equilibrium Pressures / 268	
5.6.	Getter Materials / 269	
5.6.1.	Basic Characteristics of Getter Materials / 269	
5.6.2.	Sorption Speed and Sorption Capacity / 269	
5.6.3.	Principal Types of Getter Materials and Their General Working Conditions / 271	
5.6.4.	Interaction of Getters with Common Residual Gases / 275	
5.6.5.	Evaporable Getters / 275	
5.6.5.1.	<i>Ba Getters</i> / 276	
5.6.5.2.	<i>Titanium Sublimation Getter Pumps</i> / 291	
5.6.6.	Nonevaporable Getters / 297	
5.6.6.1.	<i>Ternary Alloys</i> / 305	
5.6.6.2.	<i>Other Ternary and Multicomponent Alloys</i> / 310	

- 5.7. Getter Configurations / 310
- 5.8. Getter Applications / 313
 - 5.8.1. Nonevaporable getters versus evaporable getters / 314
 - 5.8.2. Start-up and Working Conditions of Getters / 315

Part II. Sputter Ion Pumps

317

Hinrich Henning

- 5.9. Gas Discharge Vacuum Pumps / 317
- 5.10. The Penning Discharge / 319
 - 5.10.1. Pump Sensitivity / 321
 - 5.10.2. Ion Motion / 323
 - 5.10.3. Electron Cloud / 324
 - 5.10.4. Secondary Electrons / 326
 - 5.10.5. Transition from HMF Mode to HP Mode / 327
 - 5.10.6. Transition from LMF Mode to HMF Mode / 328
 - 5.10.7. Sputtering / 329
- 5.11. SIP Characteristics / 329
 - 5.11.1. Gettering / 329
 - 5.11.2. Ion Burial / 330
 - 5.11.3. Volume Throughput / 331
 - 5.11.4. Pumping Mechanism / 335
 - 5.11.5. Bakeout / 338
 - 5.11.6. Types of SIPs / 338
 - 5.11.7. Starting Properties / 342
 - 5.11.8. Memory Effect / 343
 - 5.11.9. Ultimate Pressure / 343
 - 5.11.10. Magnets / 345

Part III. Cryopumps

347

Johan E. de Rijke

- 5.12. Adsorption-Desorption / 348
- 5.13. Cryotrapping / 352
- 5.14. Pumping Speed and Ultimate Pressure / 353
- 5.15. Capacity / 355
- 5.16. Refrigeration Technology / 357
- 5.17. Pump Configuration / 359
- 5.18. Regeneration / 363
- 5.19. Partial Regeneration / 364
- 5.20. Sorption Roughing Pumps / 364
- References / 368
- General References / 373

6. Vacuum Gauges**375***R. Norman Peacock*

- 6.1. Pressure Units Used in Vacuum Measurements / 377
- 6.2. Liquid Manometers / 378
- 6.3. McLeod Gauge / 379
- 6.4. Piston Pressure Balance Gauge / 381
- 6.5. Bourdon Gauge / 382
- 6.6. Capacitance Diaphragm Gauges / 384
 - 6.6.1. Sensitivity of the Capacitance Method / 385
 - 6.6.2. Deflection of a Thin Tensioned Membrane / 386
 - 6.6.3. Accuracy of Commercial Gauges / 387
 - 6.6.4. Thermal Transpiration / 388
 - 6.6.5. Conclusions / 388
- 6.7. Viscosity Gauges / 389
 - 6.7.1. Spinning Rotor Gauge / 391
 - 6.7.1.1. *Theory* / 391
 - 6.7.1.2. *Commercial Gauges* / 394
 - 6.7.1.3. *Stability* / 397
 - 6.7.1.4. *Secondary or Transfer Standard* / 399
 - 6.7.1.5. *Use Precautions* / 401
 - 6.7.1.6. *Advantages and Disadvantages* / 401
 - 6.7.2. Oscillating Quartz Crystal Viscosity Gauge / 402
 - 6.7.2.1. *Advantages and Disadvantages* / 402
- 6.8. Thermal Conductivity Gauges / 403
 - 6.8.1. *Theory* / 404
 - 6.8.2. *Calibration* / 406
 - 6.8.3. *Lowest Useful Pressure* / 408
 - 6.8.4. *Constant Pressure Pirani* / 409
 - 6.8.5. *Calibration Dependence Upon the Gas* / 410
 - 6.8.6. *Upper Pressure Limit* / 410
 - 6.8.7. *Ambient Temperature Compensation* / 411
 - 6.8.8. *Comparison of Pirani and Thermocouple Gauges* / 412
 - 6.8.9. *Stability* / 412
 - 6.8.10. *Thermistor Pirani Gauges and Integrated Transducers* / 412
 - 6.8.11. *Commercial Gauges and Applications* / 413
- 6.9. Ionization Gauges / 414
 - 6.9.1. *Hot-Cathode Gauge Equation* / 414
 - 6.9.2. *Geometric Variations in the Bayard–Alpert Gauge* / 419
 - 6.9.3. *Modulated Bayard–Alpert Gauge* / 421
 - 6.9.4. *Extractor Gauge* / 422
 - 6.9.5. *Helmer Gauge* / 423
 - 6.9.6. *Long Electron Path Length Gauges* / 424
 - 6.9.7. *Secondary Standard Hot-Cathode Gauges* / 425
 - 6.9.8. *High-Pressure Ionization Gauges* / 426
 - 6.9.9. *Cold-Cathode Gauges* / 427
 - 6.9.10. *Ionization Gauge Accuracy* / 435

6.9.11. Gauge Constant Ratios for Different Gases / 438

6.9.12. Ionization Gauge Controllers / 439

References / 441

7. Partial Pressure Analysis **447**

Robert E. Ellefson

7.1. Ion Sources / 447

7.1.1. Electron-Impact Ionization Process / 448

7.1.2. Open Ion Source / 449

7.1.3. Closed Ion Source / 452

7.2. Ion Detection / 454

7.2.1. Faraday Cup Ion Detection / 454

7.2.2. Secondary Electron Multiplier Detection / 454

7.2.3. Microchannel Plate Detector / 456

7.3. Mass Analysis / 456

7.3.1. Quadrupole Mass Analyzer / 456

7.3.2. Magnetic Sector Analyzer / 460

7.3.3. Time-of-Flight Mass Analyzer / 464

7.3.4. Trochoidal (Cycloid) Mass Analyzer / 465

7.3.5. Omegatron / 466

7.4. Optical Measurement of Partial Pressures / 467

7.4.1. Photoionization Measurement of Partial Pressure / 468

7.4.2. Infrared Absorption Measurement of Partial Pressure / 469

7.5. Computer Control, Data Acquisition, and Presentation / 470

7.6. Residual Gas Analysis / 471

7.7. Pressure Reduction Sampling Methods for Vacuum Process
Analysis / 474

7.8. Calibration of Partial Pressure Analyzers / 475

References / 477

8. Leak Detection and Leak Detectors **481**

Werner Grosse Bley

8.1. Principles of Vacuum Leak Detection / 482

8.1.1. Types of Leaks and Leak Rate Units / 482

8.2. Total Pressure Measurements / 484

8.3. Partial Pressure Measurements / 486

8.4. Measurement of Leakage Rates with Helium Leak Detectors / 486

8.5. Helium Leak Detection of Vacuum Components / 487

8.6. Helium Leak Detection of Vacuum Systems / 490

8.7. Special Methods and Other Tracer Gases / 493

8.8. Mass Spectrometer Leak Detectors / 493

8.8.1. Mass Spectrometer System for Helium Leak Detection / 494

8.8.2. Direct-Flow Helium Leak Detectors / 494

8.8.3. Simple Counterflow Helium Leak Detectors / 496

- 8.8.4. Advanced Counterflow Helium Leak Detectors / 498
- 8.8.5. Oil-Free and Dry Helium Leak Detectors / 499
- 8.9. Specifications of Mass Spectrometer Leak Detectors / 500
- 8.10. Quantitative Leakage Rate Measurements / 502
- 8.11. Mass Spectrometer Leak Detectors for Other Tracer Gases and Future Developments in Leak Detection / 504
- References / 505

9. High-Vacuum System Design **507**

Wolfgang Schwarz

- 9.1. Calculations of Vacuum Systems / 507
 - 9.1.1. Basic Pumpdown Equations / 508
 - 9.1.2. Process Pressure / 511
- 9.2. Gas Loads in High-Vacuum Systems / 513
 - 9.2.1. Outgassing / 513
 - 9.2.2. Leaks / 516
 - 9.2.3. Permeation / 516
 - 9.2.4. Process Gas / 518
- 9.3. Design of High-Vacuum Pump Sets / 519
 - 9.3.1. Forepump sets / 519
 - 9.3.1.1. *Fore-Vacuum Pumps* / 519
 - 9.3.1.2. *Roots Combinations* / 520
 - 9.3.2. High-Vacuum Pump Sets / 524
 - 9.3.2.1. *Turbomolecular Pump Sets* / 526
 - 9.3.2.2. *Diffusion Pump Sets* / 528
 - 9.3.2.3. *Pump Sets with Cryosurfaces* / 531
 - 9.3.2.4. *Cryopump Sets* / 535
- 9.4. Calculation Methods for Vacuum Systems / 537
 - 9.4.1. Analytical Approximations / 538
 - 9.4.2. Numerical Methods / 541
 - 9.4.2.1. *Dedicated Software* / 541
 - 9.4.2.2. *Network Approach* / 542
- General References / 546

10. Gas-Surface Interactions and Diffusion **547**

John B. Hudson

- 10.1. Adsorption / 548
 - 10.1.1. Basic Equations / 548
 - 10.1.2. Adsorption Isotherms / 551
 - 10.1.3. Heat of Adsorption / 567
 - 10.1.4. Observed Behavior / 568
 - 10.1.5. Adsorption Kinetics / 572
 - 10.1.6. Chemisorption Kinetics / 575

- 10.1.7. Kinetic Measurements / 582
- 10.1.8. Capillarity Effects / 584
- 10.2. Absorption / 589
 - 10.2.1. Equilibrium Solubility / 590
 - 10.2.2. Diffusion Rates / 590
 - 10.2.3. Kinetics of Absorption and Permeation / 591
 - 10.2.4. Steady-State Permeation / 592
 - 10.2.5. Transient Permeation / 595
 - 10.2.6. Effect of Desorption Kinetics on Permeation / 600
- 10.3. Surface Chemical Reactions / 606
- 10.4. Outgassing Behavior / 614
 - 10.4.1. Desorption of Adsorbed Gases / 614
 - 10.4.2. Dissolved Gases / 616
 - 10.4.3. Overall Pumpdown Curves / 616
 - 10.4.4. Mitigation of Outgassing / 619
 - 10.4.5. Surface Treatments During Construction / 619
 - 10.4.6. *In Situ* Surface Treatments / 620
 - 10.4.7. Bakeout Processes / 620
- References / 622

11. Ultrahigh and Extreme High Vacuum **625**
Paul A. Redhead

- 11.1. Limits to the Measurement of UHV/XHV / 628
 - 11.1.1. Residual Currents / 629
 - 11.1.2. Effects at Hot Cathodes / 636
 - 11.1.3. Gauges with Long Electron Paths / 639
 - 11.1.4. Comparison of UHV/XHV Gauges / 641
- 11.2. Limits to Pumps at UHV/XHV / 642
 - 11.2.1. Kinetic Pumps / 642
 - 11.2.2. Capture Pumps / 643
 - 11.2.3. Comparisons of Pumps for UHV/
XHV / 646
- 11.3. Leak Detection at UHV/XHV / 647
- 11.4. Outgassing / 648
 - 11.4.1. Reduction of Outgassing Rates / 648
- 11.5. UHV/XHV Hardware / 652
- References / 652

12. Calibration and Standards **657**
Karl Jousten

- 12.1. Primary Standards / 658
 - 12.1.1. Liquid Manometers and Piston Gauges / 659
 - 12.1.2. Static Expansion / 661

12.1.3. Continuous Expansion / 665	
12.1.4. Molecular Beam Expansion / 670	
12.2. Calibration by the Comparison Method / 673	
12.3. Calibration of Vacuum Gauges and Mass Spectrometers / 676	
12.3.1. Capacitance Diaphragm Gauges / 676	
12.3.2. Spinning Rotor Gauges / 680	
12.3.3. Ionization Gauges / 683	
12.3.4. Mass Spectrometers / 686	
12.4. Calibration of Test Leaks / 689	
12.5. Measurement of Pumping Speeds / 692	
References / 695	
Appendix	701
Graphic Symbols for Vacuum Components / 701	
Conversion Factors for Pressure Units / 708	
Vapor Pressure of Common Gases / 709	
Vapor Pressure of Solid and Liquid Elements / 711	
General Reference Books on Vacuum Science and Technology / 714	
Index	715